













on-resonant lifetime shortening can be attributed to the onset of stimulated emission in the disk. In fact, the 4-level system in Nd ions enables population inversion with no absorption threshold and Nd ions have a larger stimulated emission cross section than Er [15]. These two factors make lifetime shortening easier to observe in Nd resonant cavities compared to Er-doped ones. However, despite our demonstration of stimulated emission in the system, the pump power dependence of the PL at the cavity modes still exhibits a sub-linear trend (data not shown here), implying that we have not yet achieved the micro-disk lasing regime due to the large sidewall roughness losses which limit the Q-factor of the disk. However, the observation of stimulated emission in Nd:SiN<sub>x</sub> shows great promises for the engineering of on-chip lasers based on this novel materials platform.

#### **4. Conclusions**

In summary, Nd:SiN<sub>x</sub> materials were fabricated and optimized in terms of PL intensity and emission lifetime. Similar to the case of Er:SiN<sub>x</sub>, nanosecond-fast energy transfer from localized states in the bandgap of SiN<sub>x</sub> to Nd ions was observed and the role of excess Si and Nd concentration in these films discussed. The effective Nd excitation cross section for the 4-level 1.1 μm transition was measured and an active Nd:SiN<sub>x</sub> micro-disk was fabricated. Stimulated emission from the resonant modes of the disk was demonstrated under optical pumping. These results show that the Nd:SiN<sub>x</sub> materials platform bears great promises for the fabrication of Si-based laser.

#### **Acknowledgments**

This work was partially supported by the AFOSR under MURI Award No. FA9550-06-1-0470 on “Electrically-Pumped Silicon-Based Lasers for Chip-Scale Nanophotonic Systems” supervised by Dr. Gernot Pomrenke and by the NSF Career Award ECCS-0846651. Work at LLNL was performed under the auspices of the U.S. DOE by LLNL under Contract DE-AC52-07NA27344.